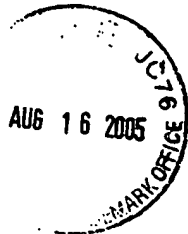


IPW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: 2813  
Examiner: Heather Doty  
Confirmation No.: 2155

In Re PATENT APPLICATION of:

Applicant(s): Hirotaka KOMATSUBARA

Serial No.: 10/765,156

Filing Date: January 28, 2004

For: METHOD FOR MANUFACTURING SOI  
LOCOS MOSFET WITH METAL OXIDE  
FILM OR IMPURITY-IMPLANTED FIELD  
OXIDE (as amended)

Atty. Docket: KAN 155

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) AMENDMENT  
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) UNDER  
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) RULE 312  
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Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Please enter the attached Replacement Sheet to correct the inadvertent submission of an explanatory sketch as a drawing change, in the last amendment. The attached sheet merely reinstates the original drawing sheet that was already approved, and removes the error of the last amendment. The Applicant regrets any inconvenience to the PTO.

Respectfully submitted,

*Nick Bromer*

August 16, 2005  
Date

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